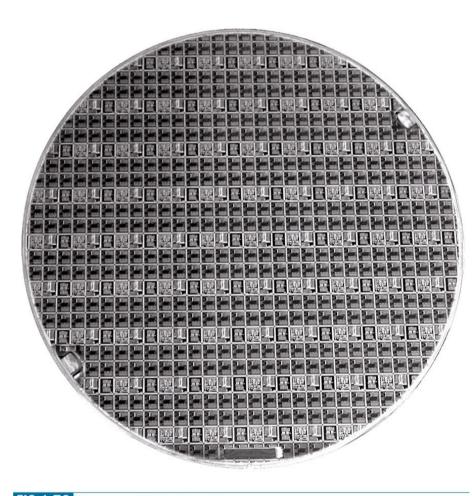
## **CMOS VLSI IC Design**

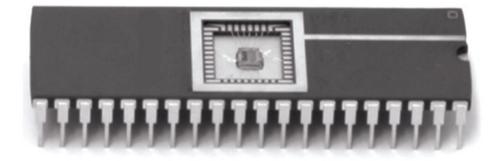
• A decent understanding of all tasks required to design and fabricate a chip takes years of experience

# Commonly used keywords

- INTEGRATED CIRCUIT (IC) many transistors on one chip
- VERY LARGE SCALE INTEGRATION (VLSI) very many transistors (> 10000 gates) on one chip
- COMPLEMENTARY METAL OXIDE SEMICONDUCTOR (CMOS) TECHNOLOGY cheap, high integration density, low power

#### **Integrated Circuits**



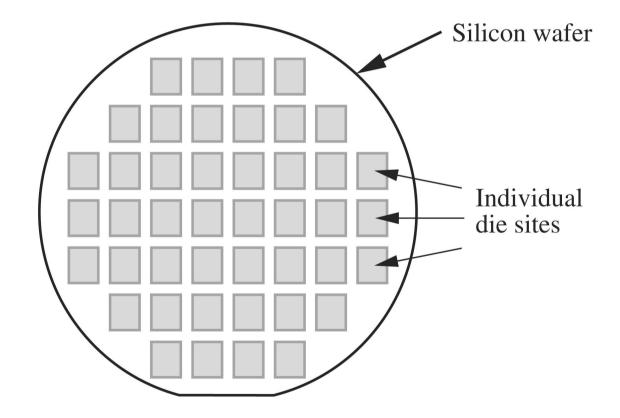


**FIG 1.71** Chip in a 40-pin dual-inline package

FIG 1.70 Processed 8-inch wafer

# The Silicon Wafer

**Figure 2.12:** Silicon wafer with individual die sites



# Packaging the Chip

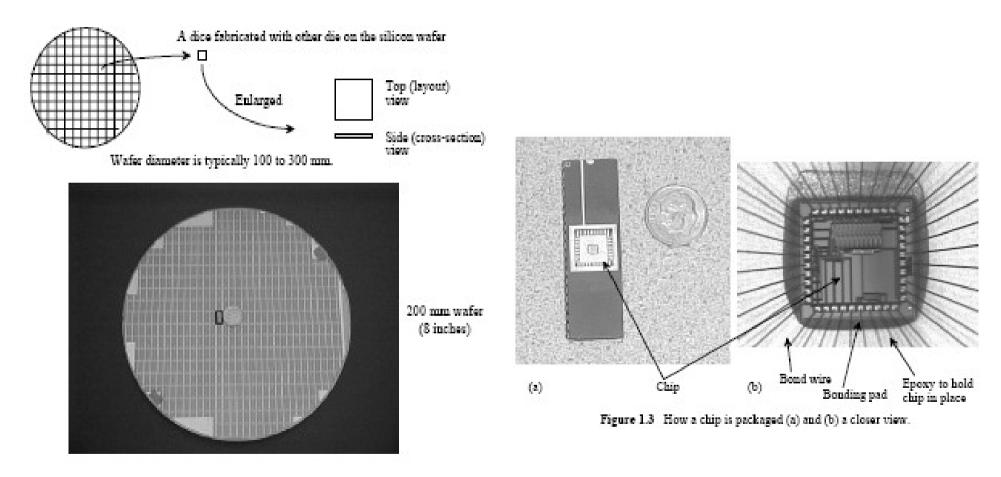


Figure 1.2 CMOS integrated circuits are fabricated on and in a silicon wafer.

# **Common Packages**

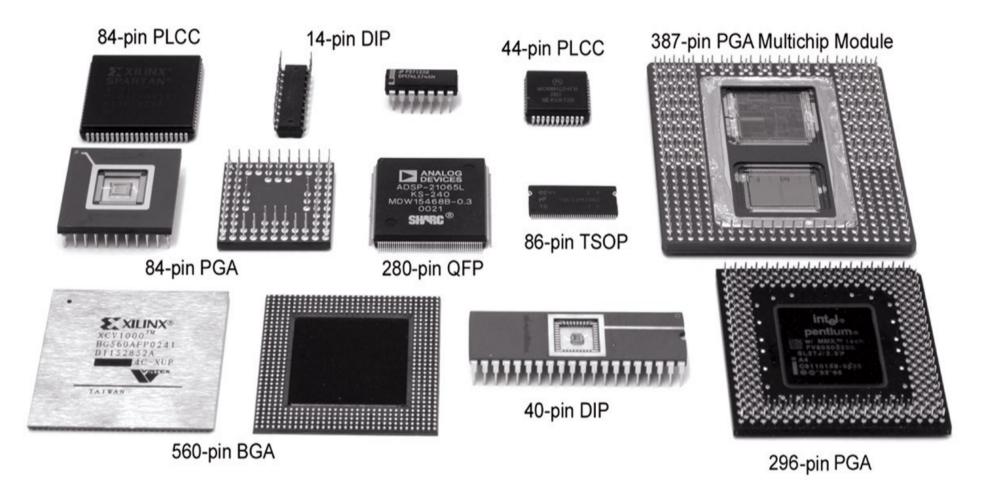
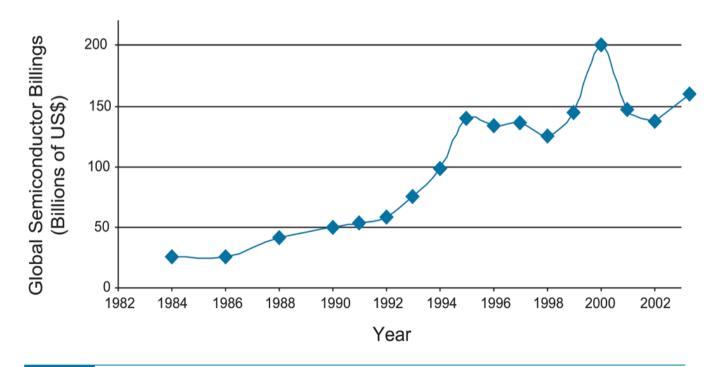


FIG 12.1 Integrated circuit packages. © 2003 Harvey Mudd College. Reprinted with permission.

# Impact of ICs industry

#### Integrated Circuits enabled today's way of life

# 10<sup>18</sup> transistors manufactured in 2003 (100 million for every human on the planet)

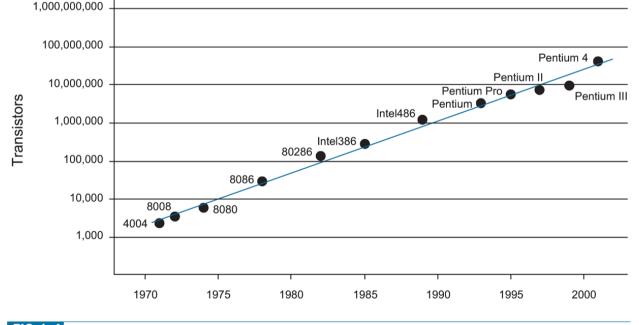


**FIG 1.1** Size of worldwide semiconductor market

Source: Semiconductor Industry Association.

## Moore's Law

- In 1963 Gordon Moore predicted that as a result of continuous miniaturization transistor count would double every 18 months
- 53% compound annual growth rate over 45 years (No other technology has grown so fast so long)



Transistors have become:

- smaller
- faster
- consume less power
- cheaper to manufacture

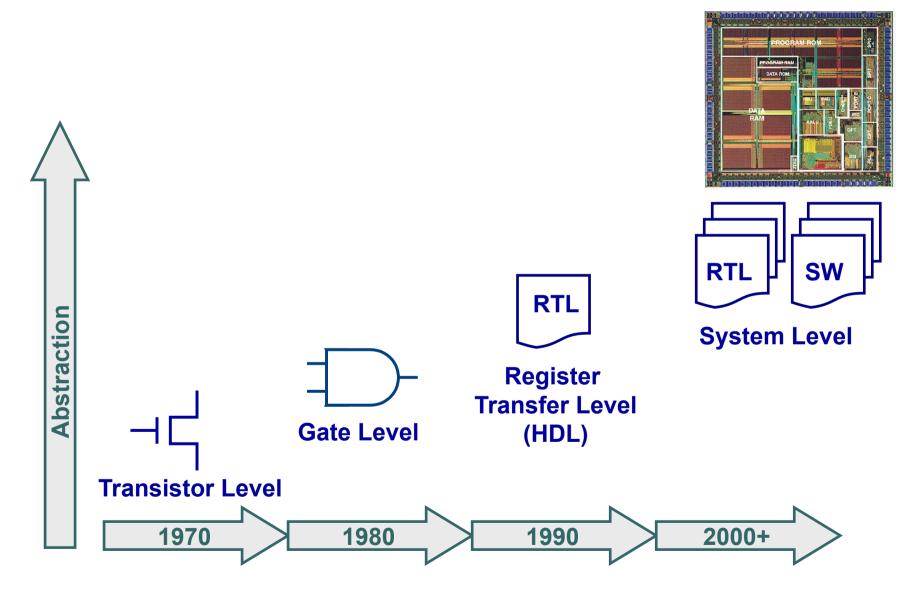




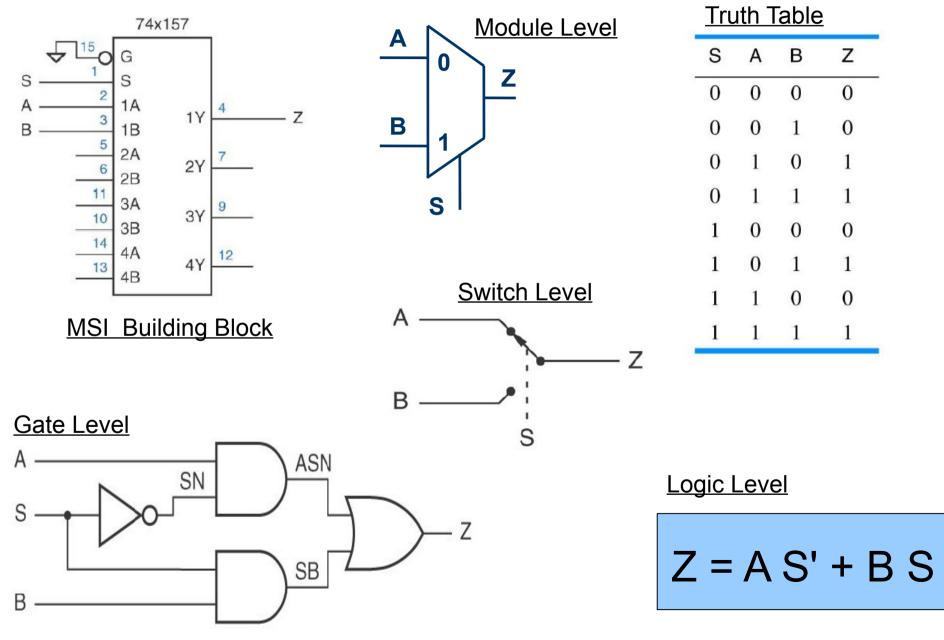
 The greatest challenge in modern VLSI design is managing system complexity

- Strategies used to cope with Complexity
  - Abstraction
  - Structured Design Approach
  - Design Flow

#### **Design Abstractions**

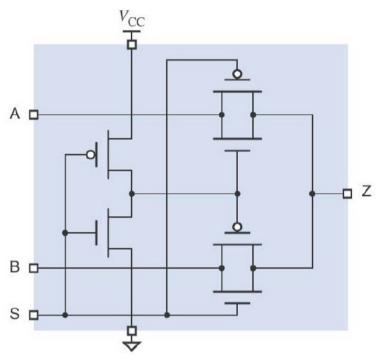


### Examples of design abstractions (1)



# **Examples of design abstractions (2)**

#### MOS transistors Level



Register Transfer Level VHDL

```
library IEEE;
use IEEE.std_logic_1164.all;
entity Vchap1mux is
    port ( A, B, S: in STD_LOGIC;
        Z: out STD_LOGIC );
end Vchap1mux;
architecture Vchap1mux_arch of Vchap1mux is
begin
    Z <= A when S = '0' else B;
end Vchap1mux_arch;
```

#### Structural Level VHDL

architecture Vchap1mux\_gate\_arch of Vchap1mux is signal SN, ASN, SB: STD\_LOGIC; -- required component declarations have been omitted -- for brevity in this example. begin U1: port map INV (S, SN); U2: port map AND2 (A, SN, ASN); U3: port map AND2 (S, B, SB); U4: port map OR2 (ASN, SB, Z); end Vchap1mux\_gate\_arch;

# **Structured Design**

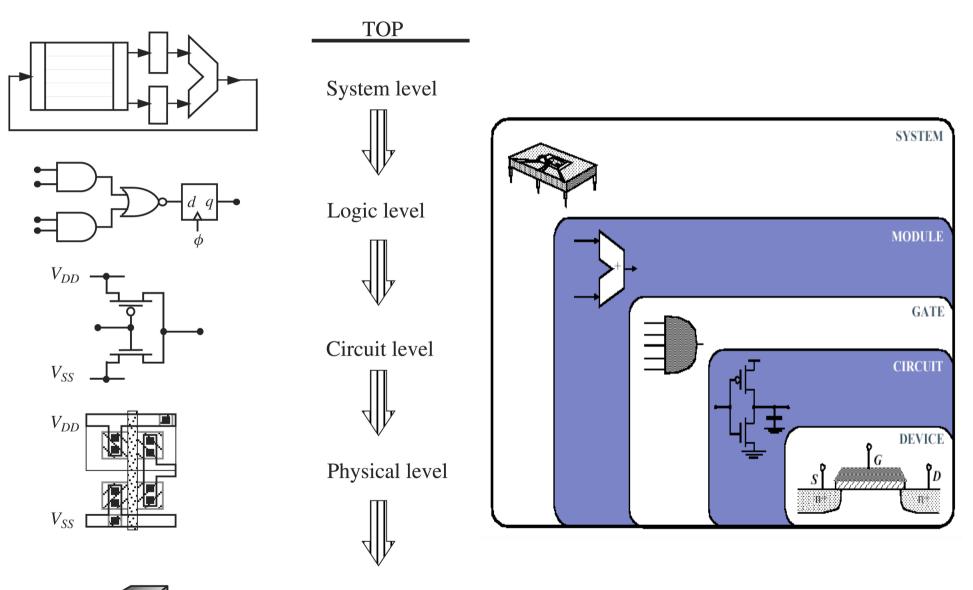
#### • Hierarchy

- Divide and Conquer paradigm
- Modularity
  - Well-defined interfaces allow modules to be treated as black boxes

#### Regularity

- It makes easier to reuse blocks
- Standard cell libraries are a very good example of modularity and regularity

# **IC Design Hierarchy**



Fabrication

BOTTOM

14

#### **Standard cells**

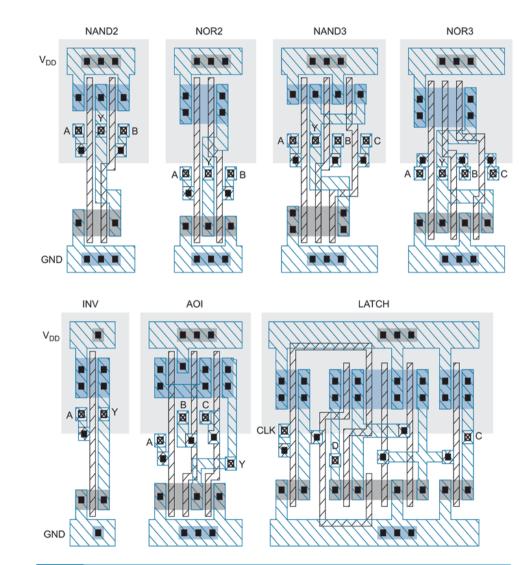
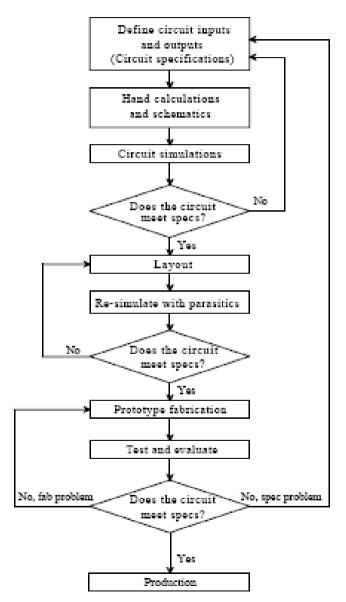


FIG 1.62 Simple standard cell library. Color version on inside front cover.

# **Simplified IC Design Flows**



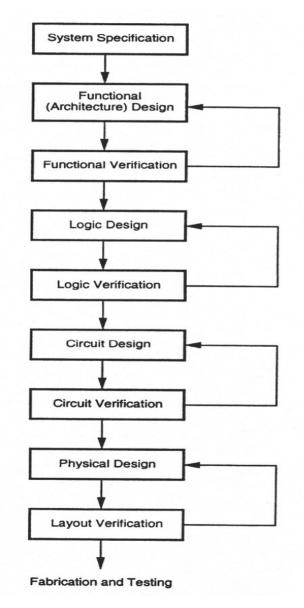
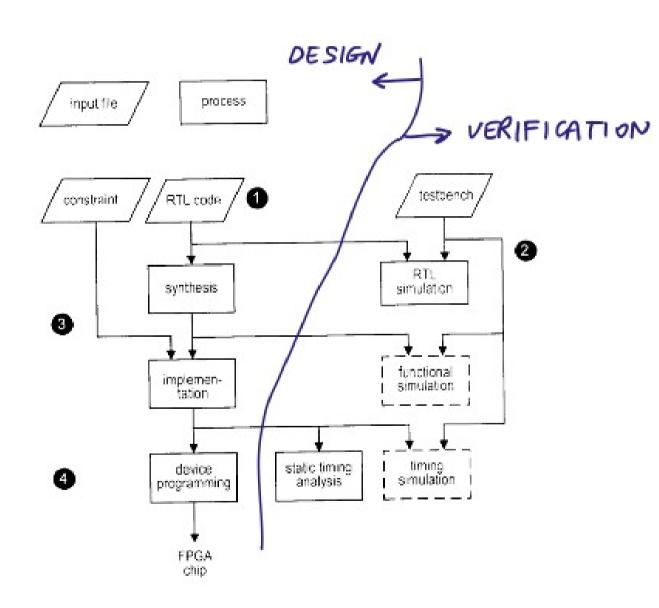


Figure 1.1 Flowchart for the CMOS IC design process.

# **Another Simplified IC Design Flow**



#### Implementation:

- Translation (merge all design files into a single netlist)
- Device mapping
- P&R

#### **Device Programming:**

- Generation conf. file
- Download conf. file into device

### **RTL code (Verilog)**

assign cout = (a&b) | (a&c) | (b&c);

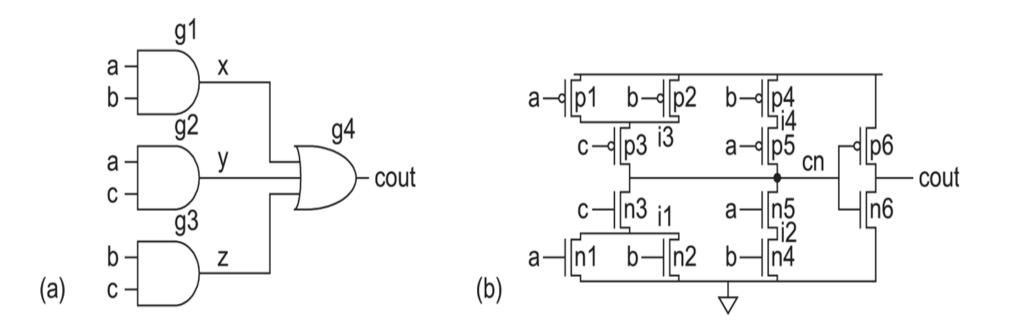
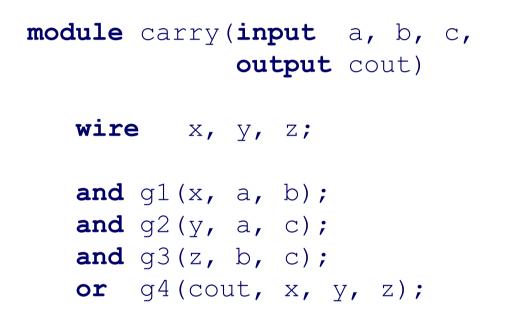
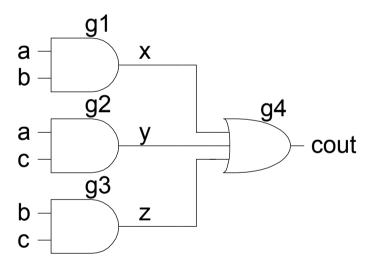


FIG 1.59 Carry subcircuit

## Gate level netlist (Verilog)



endmodule

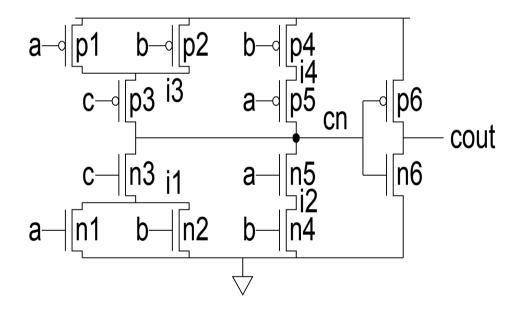


### Transistor level netlist (Verilog)

module carry(input a, b, c, output cout)

wire i1, i2, i3, i4, cn;

tranif1 n1(i1, 0, a); tranif1 n2(i1, 0, b); tranif1 n3(cn, i1, c); tranif1 n4(i2, 0, b); tranif1 n5(cn, i2, a); tranif0 p1(i3, 1, a); tranif0 p2(i3, 1, b); tranif0 p3(cn, i3, c); tranif0 p4(i4, 1, b); tranif0 p5(cn, i4, a); tranif1 n6(cout, 0, cn); tranif1 p6(cout, 1, cn);



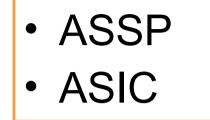
endmodule

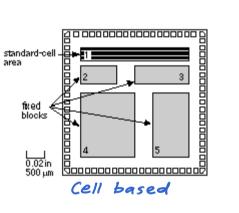
#### **SPICE** netlist

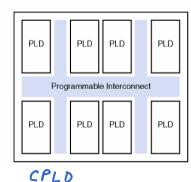
.SUBCKT CARRY A B C COUT VDD GND MN1 I1 A GND GND NMOS W=1U L=0.18U AD=0.3P AS=0.5P MN2 I1 B GND GND NMOS W=1U L=0.18U AD=0.3P AS=0.5P MN3 CN C T1 GND NMOS W=1U L=0.18U AD=0.5P AS=0.5P MN4 T2 B GND GND NMOS W=1U L=0.18U AD=0.15P AS=0.5P MN5 CN A T2 GND NMOS W=1U L=0.18U AD=0.5P AS=0.15P MP1 I3 A VDD VDD PMOS W=2U L=0.18U AD=0.6P AS=1 P MP2 T3 B VDD VDD PMOS W=2U L=0.18U AD=0.6P AS=1P MP3 CN C I3 VDD PMOS W=2U L=0.18U AD=1P AS=1P MP4 I4 B VDD VDD PMOS W=2U L=0.18U AD=0.3P AS=1P MP5 CN A T4 VDD PMOS W=2U I=0.18U AD=1P AS=0.3P MN6 COUT CN GND GND NMOS W=2U L=0.18U AD=1P AS=1P MP6 COUT CN VDD VDD PMOS W=4U L=0.18U AD=2P AS=2P CI1 I1 GND 2FF CI3 I3 GND 3FF CA A GND 4FF CB B GND 4FF CC C GND 2FF CCN CN GND 4FF CCOUT COUT GND 2FF

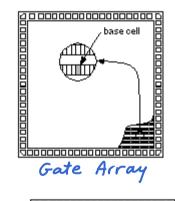
.ENDS

# Types of ICs

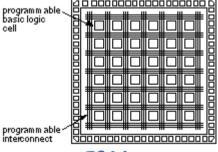








<u>Use</u>

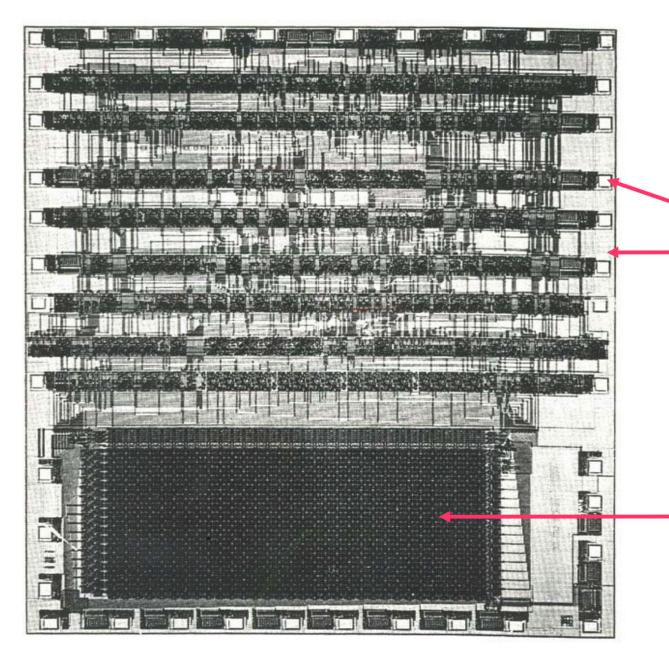




- Full-custom
- Semi-custom
  - Cell Based
  - Gate Arrays
- Programmable
  - CPLD and FPGA



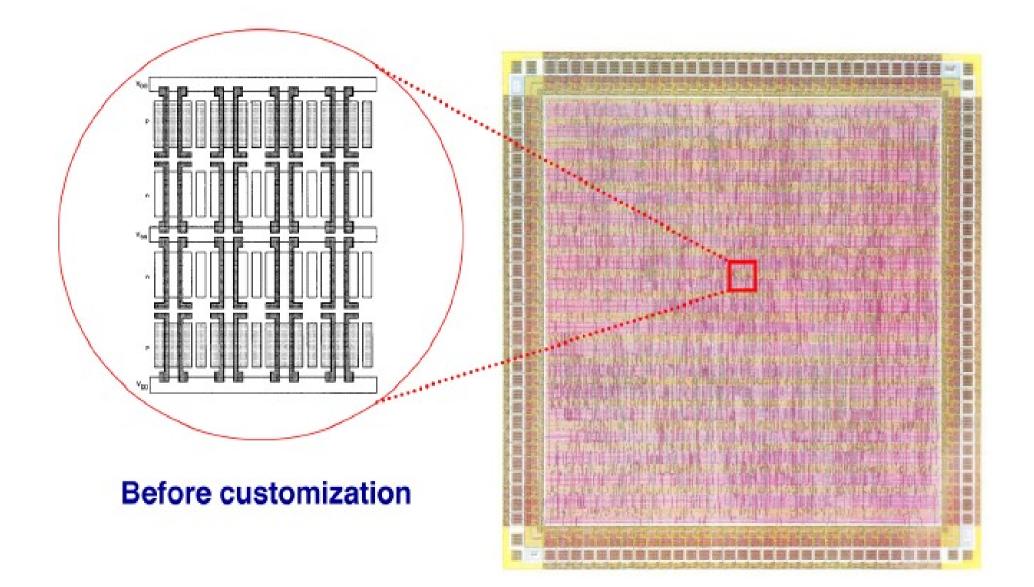
#### **Standard Cells**



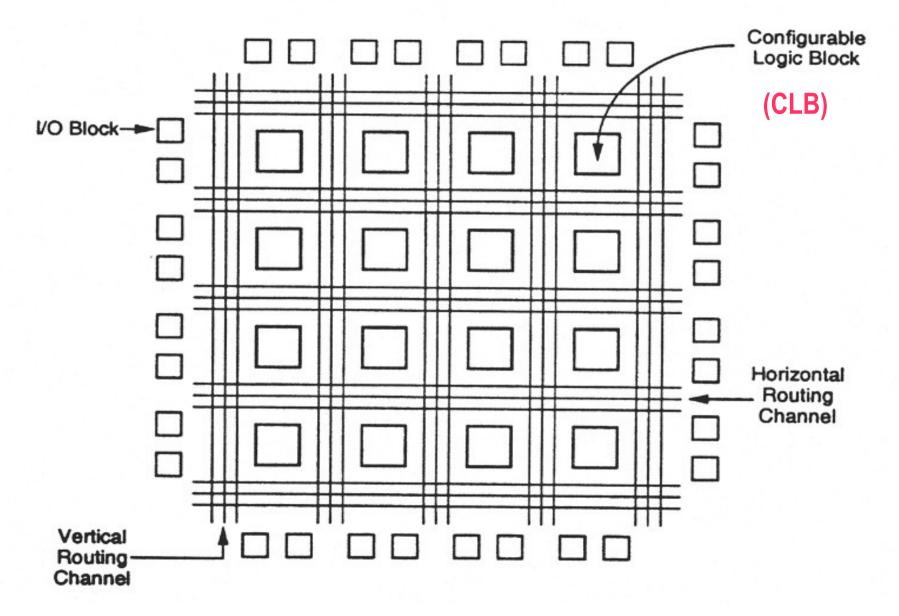
Rows of standard cells with routing channels between them

**Memory array** 

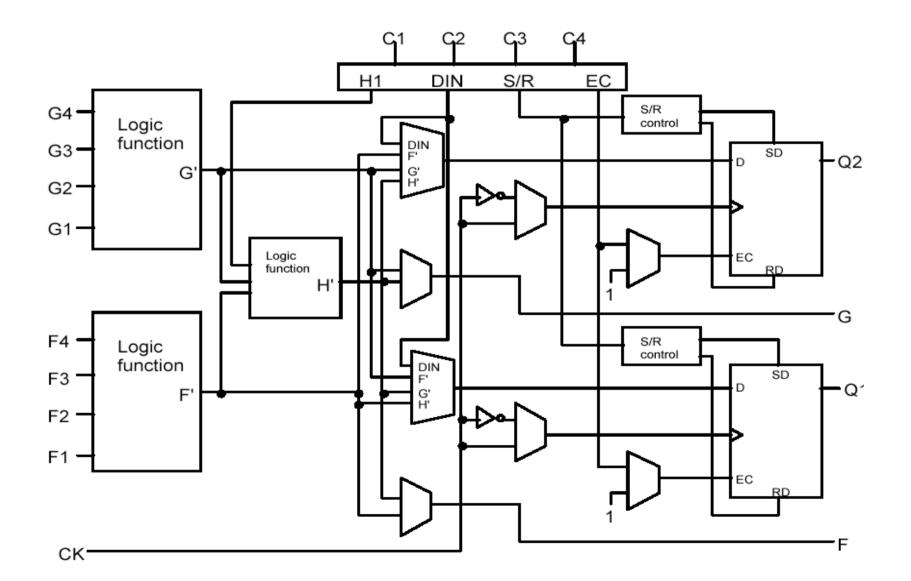
### **Gate Arrays**



#### **Field Programmable Gate Array**



### **Internal Structure of a CLB**



# Various on chip structures

- Random logic
- Data paths
- Arrays
- Analog
- Input/output (I/O)

# **Example of random Logic**

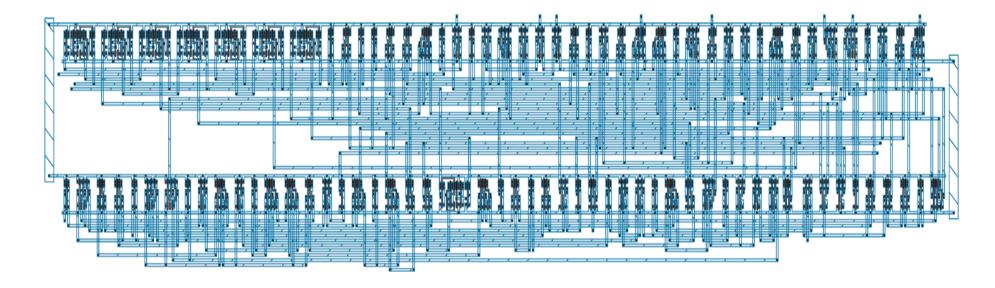


FIG 1.63 MIPS controller layout

Synthesized MIPS controller

#### Another example of random logic

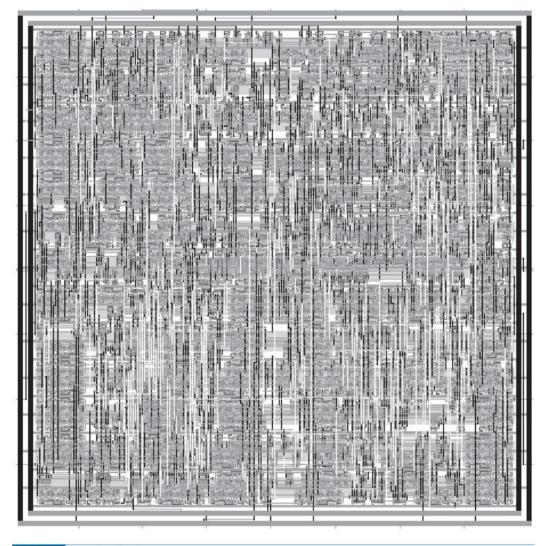
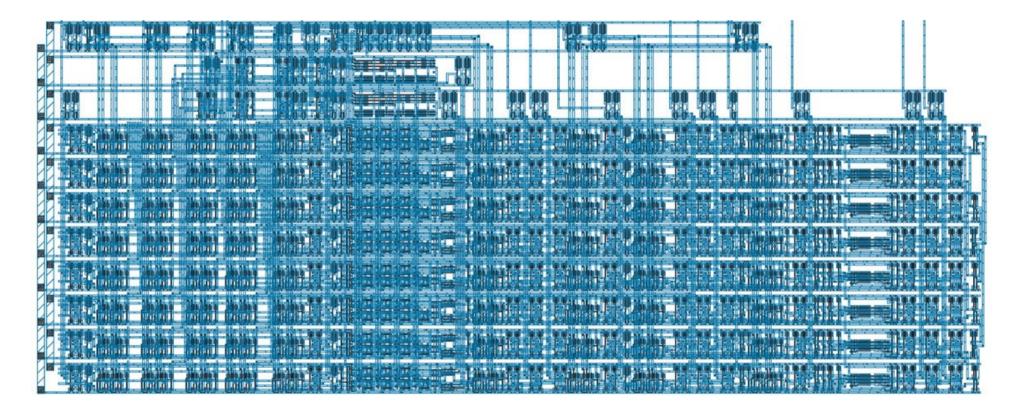


FIG 1.64 Synthesized MIPS processor

Synthesized MIPS

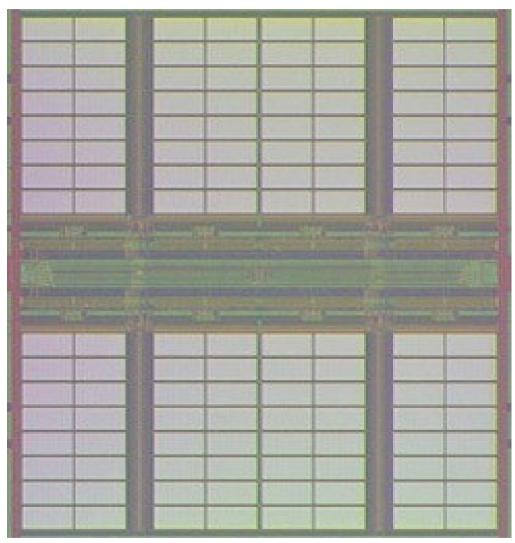
# Example of data path



#### FIG 1.66 MIPS datapath layout

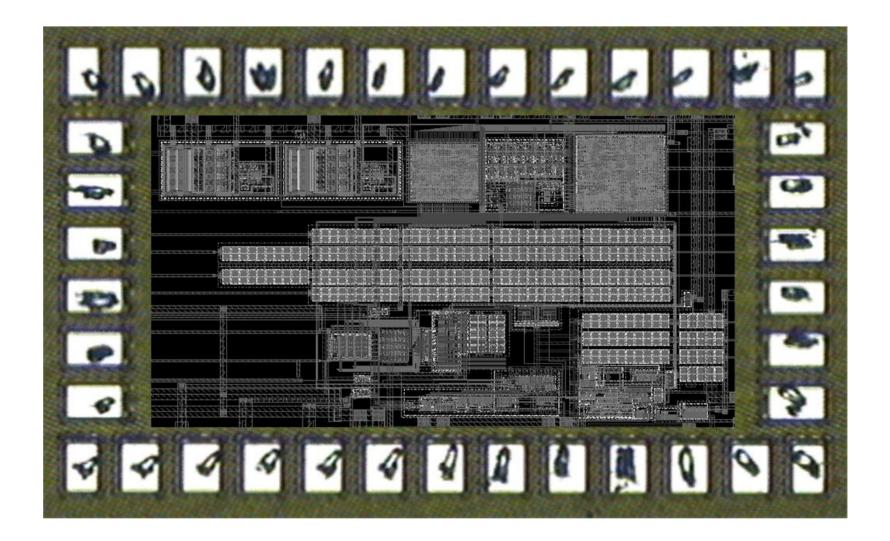
Hand-Crafted MIPS datapath

### **Example of Array**



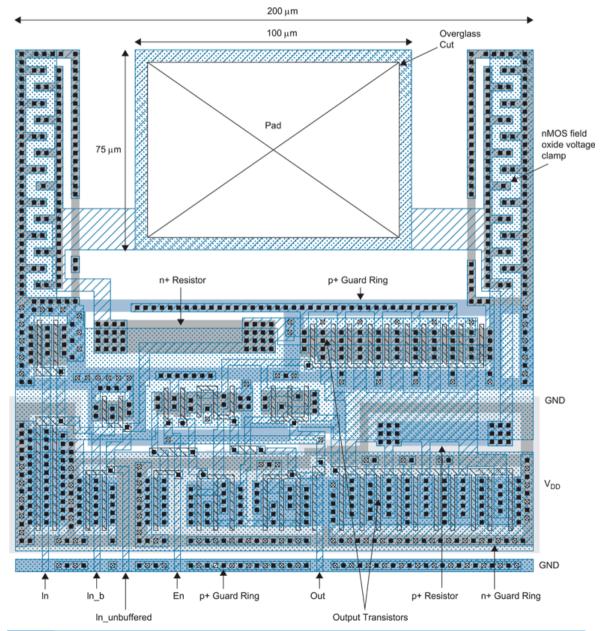
• SRAM chip

### **Example of Analog structure**



Charge Pump Phase-Locked Loop

## Example of I/O



# **Bidirectional I/O PAD circuit**

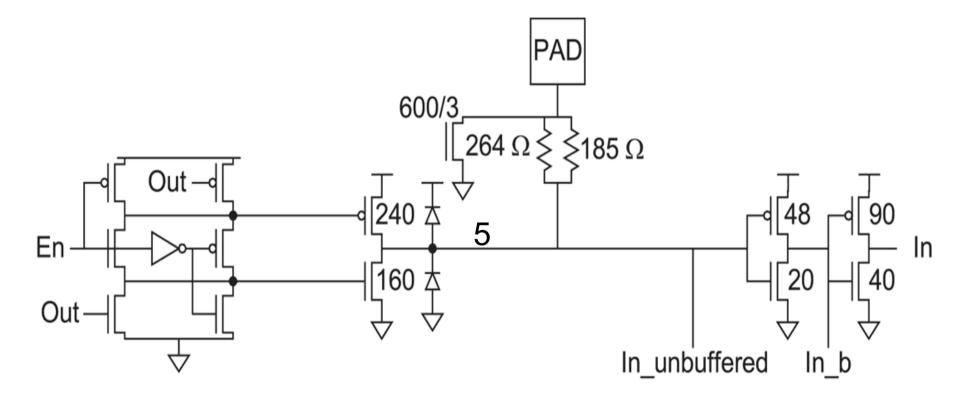


FIG 12.24 MOSIS bidirectional pad schematic

# **Physical Design**

- Floorplanning and area estimation
- Standard Cell Based Layout
  - Place and Route
  - Parasitic Extraction
  - Post Layout Verification
- Data-path Based Layout
  - Slice Planning
  - Parasitic Extraction
  - Post Layout Verification

# Floorplanning

- Does the design fit the chip area budgeted ?
- Estimates area of major units and defines their relative placement
- Estimate wire lengths
- Estimate wiring congestion

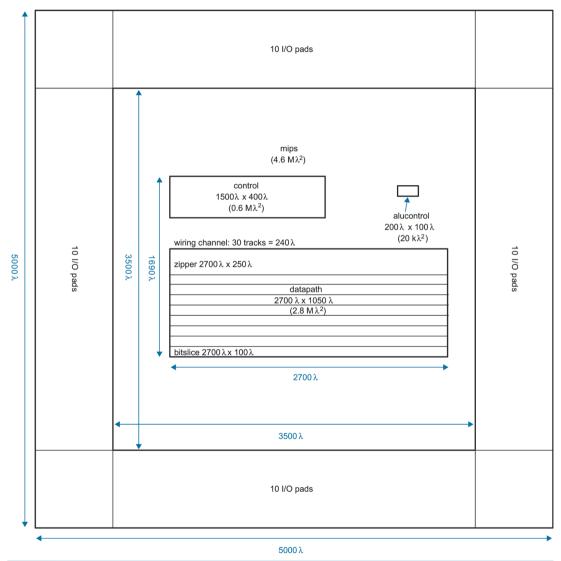


FIG 1.60 MIPS floorplan

# **Area Estimation**

• Some cell library vendor specify cell layout densities in Kgates/mm<sup>2</sup>

Table 1.10Typical layout densities	
Element	Area
random logic (2-level metal process)	$1000 - 1500 \lambda^2$ / transistor
datapath	$250 - 750 \lambda^2$ / transistor
	or 6 WL + 360 $\lambda^2$ / transistor
SRAM	1000 $\lambda^2$ / bit
DRAM (in a DRAM process)	100 $\lambda^2$ / bit
ROM	$100 \lambda^2$ / bit

- Compare to another block you already designed or estimate from transistor counts
- Budget room for large wiring tracks

# **Example of Layout**

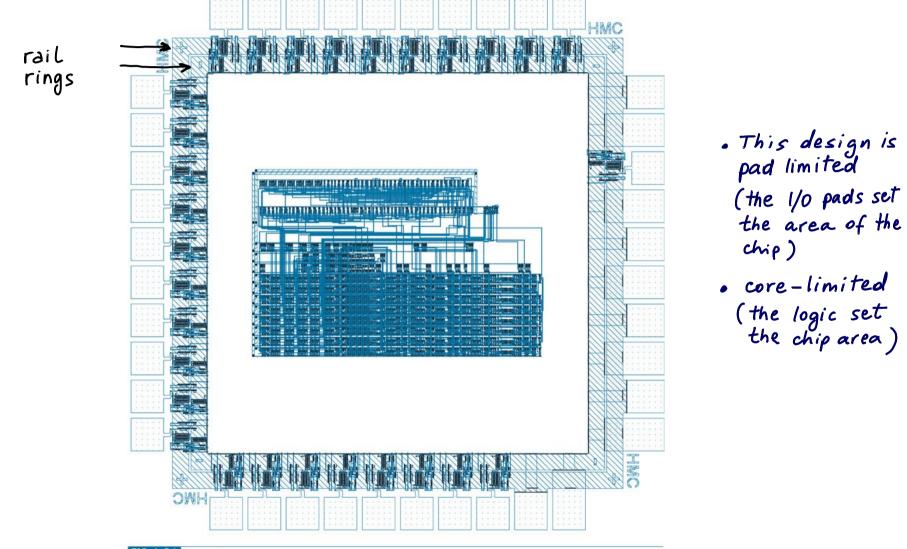
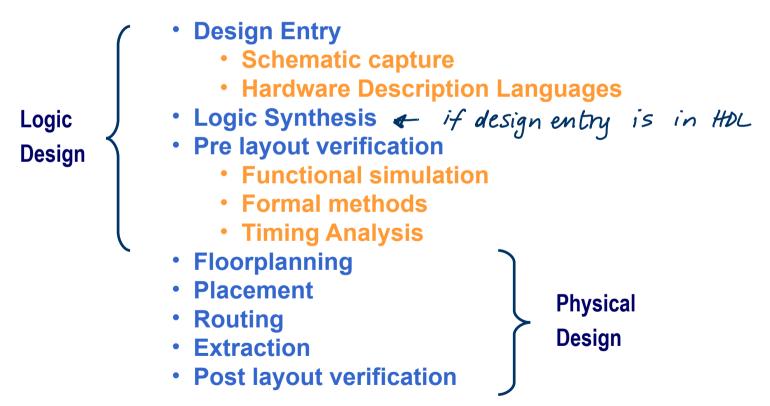


FIG 1.61 MIPS layout

# **CAD Tools**

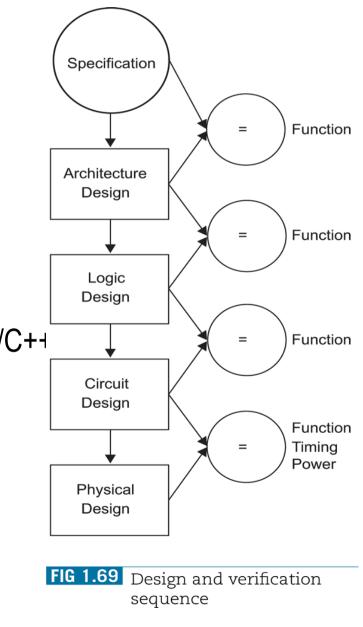
 Designers rely increasingly on design automation software tools to seek productivity gains and to cope with increased complexity

#### **Typical Design Flow**



# Verification

- Fabrication is slow & expensive
- MOSIS 0.6µm masks: \$1000, 3 months
- State of art masks (130nm): \$1M, 1 month
- Debugging chips is very hard
- Limited visibility into operation
- Prove design is right before building!
- System simulation & performance Assessment (C/C++
- Logic Simulation / formal verification / STA
- Circuit simulation
- Layout vs. schematic comparison (LVS)
- Design & electrical rule checks (DRC, ERC)
- Verification is > 50% of effort on most chips !



# Fabrication

- Tapeout final layout
  - Formats for mask descriptions:
     CIF (academia) and GDS II (industry)
- Fabrication

FIG 1.70 Processed 8-inch wafer

- 6, 8, 12" wafers (bare wafer costs \$1000-\$5000)
- Optimized for throughput, not latency (turnaround times up to 10 weeks !)
- Cut into individual dice
- Fabs cost billions of dollars and become obsolete in a few years
  - Fabless semiconductor companies
  - Manufacturing Companies: TSMS, UMC, IBM

# Testing

- Test that chip operates as expected
  - Design errors
  - Manufacturing errors
- A single dust particle or wafer defect kills a die
  - Yields from 90% to < 10%
  - Depends on die size, maturity of process
  - Test each part before shipping to customer

# Summary

- Chip Design requires a fundamental understanding of circuit and physical design
- This is true even if many chip designers spend much of their time specifying circuits with HDL and seldom look at the actual transistors

• The best way to learn VLSI design is by doing it !

# MOS Transistors (POS to be picky)

- TRANS-ISTOR (=TRANSFER-RESISTOR)
- Four terminals: gate, source, drain, body (= bulk)

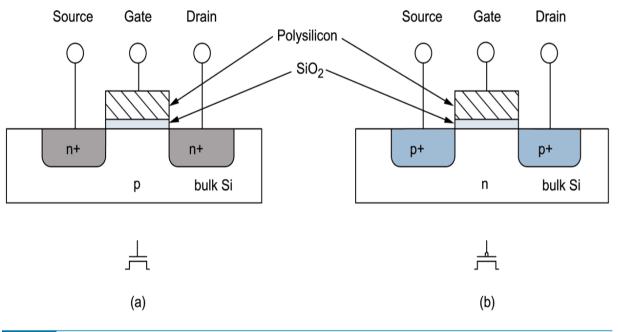


FIG 1.8 nMOS transistor (a) and pMOS transistor (b)

#### **Our first CMOS circuit**

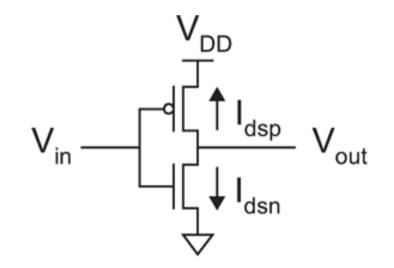


FIG 2.23 A CMOS inverter